STUDY OF SURFACE PASSIVATIONS ON HPGe DETECTORS

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Outlines

- \geq Characterization by γ -spectroscopy of a planar HPGe detector prototype
- > Study of the passivated surface with low energy γ -ray
- > Comparison between different passivation processes:



New experimental set-up

Several HPGe detector passivations have been realized in the LNL's Materials Laboratory and a new experimental setup has been constructed to allow a better study of their properties.

- Always the same planar HPGe n-type crystal (21 mm height - 39 mm diameter)
- Reduced lateral thickness of the mounting cap
- Lead collimator on a micromotional device



Measurements

After every passivation procedure, the detector was mounted in the special cryostat, cooled and subjected to a complete characterization with γ sources.

Two different kinds of measurements:

 determination of detector bulk properties by putting different standard calibration γ sources in front of the end cap;

Scanning of the lateral intrinsic surface by irradiating from the side of the crystal with an ²⁴¹Am collimated source on a micrometrical motion device that moves with 0.6 mm steps





Determination of:

the best response working voltage or depletion voltage V_d, defined as the reverse bias voltage required to extend the depletion region through the full thickness of the semiconductor bulk

the energy resolution for the 1.33 MeV ⁶⁰Co peak as a function of voltage

> the detector efficiency as a function of the radiation energy



Depletion voltage V_d

- The depletion voltage is not the same for the different passivations:
 2000V for the sulfide,
 1700V for the methanol and 1500V for the two hydrides
- The counting rate at the plateau is different for the sulfide: it was proved to be related to a smaller active volume

- ⁶⁰*Co* source, in front of the detector
- Integrals of the peak at 1.33 MeV, normalized to the acquisition live times





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Depletion voltage V_d

The depletion voltage is essentially the same for these three passivation methods, as well as the final plateau value

- ⁶⁰Co source, in front of the detector
- Integrals of the peak at 1.33 MeV, normalized to the acquisition live times





Energy resolution

The best resolution does not depend on the passivation, it is essentially the same for all the methods [1.74-1.79 keV]

- ⁶⁰*Co* source, in front of the detector
- Resolution (FWHM) of the peak at 1.33 MeV





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Energy resolution

The best resolution is essentially the same for all these three methods, as well as the voltage at which those resolution are reached

Passiv.	Depletion Voltage [V]	Best resolution Voltage [V]	Best resolution [keV]
Low H	1500	1500	1.74
High H	1500	1500	1.75
Hyper H	1500	1500	1.77

- ⁶⁰*Co* source, in front of the detector
- Resolution (FWHM) of the peak at 1.33 MeV





Efficiency

The efficiency shows not to depend on the H-type passivation process and it is comparable with the expected values and with the results of the other passivations - Different standard sources, in front of the detector



Lateral scanning with collimated source for the:

determination of the dead layer below the lateral surface induced by the passivation, estimated starting from the counting rate and applying the Beer-Lambert law for γ rays absorption

Study of the Am spectra as a function of the distance between the collimated γ beam and the detector contacts, for each passivation treatment at its best resolution voltage and in some cases at different voltages





S passivation is the most used in microelectronics because it's stable, but it has the larger dead layer

Li		
n* contact HPGe crystal	p* contact Au electrode	

- ²⁴¹*Am* collimated source, from the side of the detector
- Integrals of the full-energy peak at 59.54 keV, normalized to the acquisition live times





The counting rate in:

- Low-H passivation decreases moving from the n⁺ to p⁺ contact, giving rise to a slightly ntype surface;
- High-H passivation increases from n⁺ to p⁺ contact, giving rise to a slightly p-type surface;
- Hyper-H passivation remains constant along all the scan, giving rise to an ideal passivation.

- ^{241}Am collimated source, from the side of the detector
- Integrals of the full-energy peak at 59.54 keV, normalized to the acquisition live times





The counting rate in:

- Low-H passivation decreases moving from the n⁺ to p⁺ contact, giving rise to a slightly ntype surface;
- High-H passivation increases from n⁺ to p⁺ contact, giving rise to a slightly p-type surface;
- Hyper-H passivation remains constant along all the scan, giving rise to an ideal passivation.

- Dead layer thickness determination from the counting rates applying the Beer-Lambert law for gamma absorption





Background and resolution

An increase of the background contribution to the spectra with the dead layer thickness is observed for all the different passivations



 ^{241}Am collimated source, from the side of the detector





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 ^{241}Am collimated source, from the side of the detector



Conclusions

- > The efficiency, the depletion voltage and the energy resolution of the detector are comparable for the three H-terminated passivations
- The estimated dead layers induced below the passivated surfaces are thinner and more homogeneous than the ones of common commercial detectors, but they have presented different trends: the Hyper H termination is the most uniform

Collaborators

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THANK YOU FOR THE ATTENTION